## **CLAIMS**

What is claimed is:

1. A multi-layer structure comprising:

a substrate; and

a transformation layer formed on the substrate,

wherein a volume of a portion of the transformation layer irradiated by a laser beam changes when a temperature of the portion exceeds a predetermined temperature.

- 2. The multi-layer structure of claim 1, wherein the substrate is made from glass (SiO<sub>2</sub>) or polycarbonate.
- 3. The multi-layer structure of claim 1, wherein the transformation layer comprises an alloy dielectric layer made of alloy and dielectric material.
- 4. The multi-layer structure of claim 3, wherein the alloy contains a rare-earth metal and a transition metal.
- 5. The multi-layer structure of claim 3, wherein the alloy dielectric layer is made from an alloy and a dielectric material whose volumes change due to interdiffusion or chemical change resulting from heating.
- 6. The multi-layer structure of claim 3, wherein the transformation layer further comprises a dielectric layer sandwiched between the substrate and the alloy dielectric layer.
  - 7. The multi-layer of claim 3, wherein the dielectric material is ZnS-SiO<sub>2</sub>.
  - 8. The multi-layer of claim 3, wherein the alloy is TbFeCo.
  - 9. The multi-layer of claim 3, wherein the alloy is NdFeCo.

10. The multi-layer structure of claim 1, wherein the transformation layer comprises a metal oxide layer.

- 11. The multi-layer structure of claim 10, wherein the metal oxide layer contains a transition metal or a noble metal.
- 12. The multi-layer structure of claim 10, wherein the metal oxide layer is made from a material whose volume changes by releasing oxygen when heated.
- 13. The multi-layer structure of claim 10, wherein the transformation layer further comprises a dielectric layer sandwiched between the substrate and the metal oxide layer.
- 14. The multi-layer structure of claim 13, wherein the dielectric layer is made from ZnS-SiO<sub>2</sub>
- 15. The multi-layer structure of claim 13, wherein the metal oxide layer is made of WO<sub>x</sub>.
- 16. The multi-layer structure of claim 13, wherein the metal oxide layer has a thickness of about 80 nm.
  - 17. The multi-layer structure of claim 1, wherein the transformation layer comprises: a first dielectric layer formed on the substrate; an alloy layer overlying the first dielectric layer; and a second dielectric layer overlying the alloy layer.
- 18. The multi-layer structure of claim 17, wherein the first dielectric layer is made from a mixture of zinc sulfide (ZnS) and silicon dioxide (SiO<sub>2</sub>).
- 19. The multi-layer structure of claim 17, wherein the first dielectric layer has a thickness of about 50 to 250 nm.
- 20. The multi-layer structure of claim 17, wherein the alloy layer has a thickness of about 5 to 50 nm.

21. The multi-layer structure of claim 17, wherein the alloy layer contains a rare-earth metal and a transition metal.

- 22. The multi-layer structure of claim 21, wherein the rare earth metal is terbium (Tb) or neodymium (Nd), and the transition metal is iron (Fe) or cobalt (Co).
- 23. The multi-layer structure of claim 17, wherein the alloy layer is made from a material that changes volumes of the alloy layer and the first and second dielectric layers by causing interdiffusion or chemical change with the first and second dielectric layers upon heating.
- 24. The multi-layer structure of claim 23, wherein the alloy layer is made from terbium-iron-cobalt (TbFeCo).
- 25. The multi-layer structure of claim 23, wherein the alloy layer is made from neodymium-iron-cobalt (NdFeCo).
- 26. The multi-layer structure of claim 17, wherein the second dielectric layer is made from a mixture of zinc sulfide (ZnS) and silicon dioxide (SiO<sub>2</sub>).
- 27. The multi-layer structure of claim 17, wherein the second dielectric layer has a thickness of about 10 to 100 nm.
  - 28. The multi-layer structure of claim 1, wherein the transformation layer comprises:
  - a first dielectric layer formed on the substrate;
  - a metal oxide layer overlying the first dielectric layer; and
  - a second dielectric layer overlying the metal oxide layer.
- 29. The multi-layer structure of claim 28, wherein the metal oxide layer contains a transition metal or a noble metal.
- 30. The multi-layer structure of claim 29, wherein the noble metal is one of platinum oxide (PtO<sub>x</sub>), silver oxide (AgO<sub>x</sub>), palladium oxide (PdO<sub>x</sub>), and tungsten oxide (WO<sub>x</sub>).

31. The multi-layer structure of claim 28, wherein the metal oxide layer is made from a material whose volume changes by releasing oxygen when heated.

32. A method of drawing a microscopic structure on a multi-layer structure including a substrate and a transformation layer formed on the substrate, wherein a volume of a predetermined region of the transformation layer irradiated by a laser beam changes when a temperature of the region exceeds a predetermined temperature, the method comprising:

emitting the laser beam onto the predetermined region of the transformation layer; and heating the region of the transformation layer irradiated by the laser beam beyond the predetermined temperature,

wherein the heated region undergoes the volume change.

- 33. The method of claim 32, wherein the transformation layer comprises a metal oxide layer.
  - 34. The method of claim 32, wherein the transformation layer comprises: a first dielectric layer formed on the substrate; an alloy layer overlying the first dielectric layer; and a second dielectric layer overlying the alloy layer.
  - 35. The method of claim 32, wherein the transformation layer comprises: a first dielectric layer formed on the substrate; a metal oxide layer overlying the first dielectric layer; and a second dielectric layer overlying the metal oxide layer.
- 36. The method of claim 32, further comprising etching the transformation layer using a difference in etch rate between the predetermined region and a remaining region.
  - 37. A master for manufacturing an optical disc, the master comprising:
  - a substrate; and
  - a transformation layer formed on the substrate,

wherein a volume of a portion of the transformation layer irradiated by a laser beam changes when a temperature of the portion exceeds a predetermined temperature.

38. The master of claim 37, wherein the transformation layer comprises an alloy dielectric layer made of alloy and dielectric material.

- 39. The master of claim 38, wherein the alloy contains a rare-earth metal and a transition metal.
- 40. The master of claim 38, wherein the alloy dielectric layer is made from an alloy and a dielectric material whose volumes change due to interdiffusion or chemical change resulting from heating.
- 41. The master of claim 38, wherein the transformation layer further comprises a dielectric layer sandwiched between the substrate and the alloy dielectric layer.
- 42. The master of claim 37, wherein the transformation layer comprises a metal oxide layer.
- 43. The master of claim 42, wherein the metal oxide layer contains a transition metal or a noble metal.
- 44. The master of claim 42, wherein the metal oxide layer is made from a material whose volume changes by releasing oxygen when heated.
- 45. The master of claim 42, wherein the transformation layer further comprises a dielectric layer sandwiched between the substrate and the metal oxide layer.
  - 46. The master of claim 37, wherein the transformation layer comprises: a first dielectric layer formed on the substrate; an alloy layer overlying the first dielectric layer; and a second dielectric layer overlying the alloy layer.
- 47. The master of claim 46, wherein the alloy layer contains a rare-earth metal and a transition metal.

48. The master of claim 46, wherein the alloy layer is made from a material such that volumes of the alloy layer and the first and second dielectric layers change due to interdiffusion or chemical change resulting from heating.

- 49. The master of claim 37, wherein the transformation layer comprises:
- a first dielectric layer formed on the substrate;
- a metal oxide layer overlying the first dielectric layer; and
- a second dielectric layer overlying the metal oxide layer.
- 50. The master of claim 49, wherein the metal oxide layer contains a transition metal or a noble metal.
- 51. The master of claim 49, wherein the metal oxide layer is made from a material whose volume changes by releasing oxygen when heated.
- 52. A method of manufacturing a master including a substrate and a transformation layer formed on the substrate, wherein a volume of a predetermined region of the transformation layer irradiated by a laser beam changes when a temperature of the predetermined region exceeds a predetermined temperature, the method comprising:

emitting the laser beam onto the predetermined region of the transformation layer; and heating the region of the transformation layer irradiated by the laser beam beyond the predetermined temperature,

wherein the heated region undergoes the volume change.

- 53. The method of claim 52, wherein the transformation layer comprises a metal oxide layer.
  - 54. The method of claim 52, wherein the transformation layer comprises: a first dielectric layer formed on the substrate; an alloy layer overlying the first dielectric layer; and a second dielectric layer overlying the alloy layer.
  - 55. The method of claim 52, wherein the transformation layer comprises: a first dielectric layer formed on the substrate;

a metal oxide layer overlying the first dielectric layer; and a second dielectric layer overlying the metal oxide layer.

- 56. The method of claim 52, further comprising etching the transformation layer using a difference in etch rate between the predetermined region and a remaining region.
- 57. A computer readable medium encoded with processing instructions for performing a method of drawing a microscopic structure on a multi-layer structure including a substrate and a transformation layer formed on the substrate, wherein a volume of a predetermined region of the transformation layer irradiated by a laser beam changes when the temperature of the region exceeds a predetermined temperature, the method comprising:

emitting the laser beam onto the predetermined region of the transformation layer; and heating the region of the transformation layer irradiated by the laser beam beyond the predetermined temperature,

wherein the heated region undergoes the volume change.

- 58. The computer readable medium of claim 57, wherein the transformation layer comprises:
  - a first dielectric layer formed on the substrate; an alloy layer overlying the first dielectric layer; and a second dielectric layer overlying the alloy layer.
- 59. The computer readable medium of claim 57, wherein the transformation layer comprises:
  - a first dielectric layer formed on the substrate;
  - a metal oxide layer overlying the first dielectric layer; and
  - a second dielectric layer overlying the metal oxide layer.
- 60. The computer readable medium of claim 57, further comprising etching the transformation layer using a difference in etch rate between the predetermined region and the remaining region.

61. A computer readable medium encoded with processing instructions for performing a method of manufacturing a master including a substrate and a transformation layer formed on the substrate, wherein a volume of a predetermined region of the transformation layer irradiated by a laser beam changes when a temperature of the predetermined region exceeds a predetermined temperature, the method comprising:

emitting the laser beam onto the predetermined region of the transformation layer; and heating the region of the transformation layer irradiated by the laser beam beyond the predetermined temperature,

wherein the heated region undergoes the volume change.

62. A method of drawing a microscopic structure on a multi-layer structure including a substrate and a transformation layer formed on the substrate, wherein a volume of a predetermined region of the transformation layer irradiated by a laser beam changes when a temperature of the region exceeds a predetermined temperature, the method comprising:

emitting the laser beam onto the predetermined region of the transformation layer; and heating the region of the transformation layer irradiated by the laser beam beyond the predetermined temperature,

wherein a diameter of the heated region is smaller that a diameter of the laser beam thus forming a pit with a diameter smaller than that of a laser beam spot.

63. A method of drawing a microscopic structure on a multi-layer structure including a substrate and a transformation layer formed on the substrate, wherein a volume of a predetermined region of the transformation layer irradiated by a laser beam changes when a temperature of the region exceeds a predetermined temperature, the method comprising:

emitting the laser beam onto the predetermined region of the transformation layer; and heating the region of the transformation layer irradiated by the laser beam beyond the predetermined temperature,

wherein a pit pattern with a size smaller than a diffraction limit of the laser beam is formed on the multi-layer structure.

64. The multi-layer structure of claim 17, wherein the first dielectric layer, the alloy layer and the second dielectric layer are combined into a single structure.

65. The multi-layer structure of claim 10, wherein the metal oxide layer is formed directly on the substrate.

66. The method of claim 32, further comprising:

injection-molding a polycarbonate optical disc substrate in an injection-molding apparatus and sequentially coating a reflective layer and a protective layer over the injection-molded substrate.

- 67. The method of claim 32, wherein microscopic pits having a size smaller than a diffraction limit of the laser beam are created, without requiring a large light source or causing the deformation of evaporation of a resist material due to elevated temperature.
- 68. A method of forming a pit pattern on a multi-layer structure including a substrate and a transformation layer formed on the substrate, the method comprising:

changing a volume of a predetermined region of the transformation layer by irradiating a laser beam onto the predetermined region of the transformation layer; and

forming the pit pattern on the multi-layer structure, the pit pattern having a size smaller than a diffraction limit of the laser beam.

- The method of claim 68, wherein the volume of the predetermined region changes by heating the predetermined region beyond a predetermined temperature.
  - 70. An apparatus forming optical discs, the apparatus comprising:

a stamper molding an optical disc substrate, the stamper having a pit pattern smaller than a diffraction limit of a laser beam used to form the pit pattern; and

a coater coating a reflective layer and a protective layer over the molded optical disc substrate.